

Tuning electronic band topology of rare-earth monopnictides

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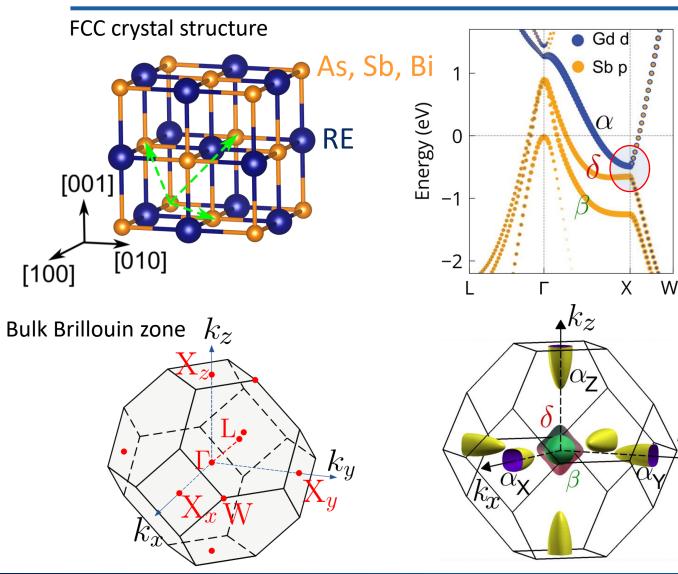






RE-V: a semimetallic with many interesting properties





- Compensated semimetalics used for spintronics, thermoelectric materials, low contact resistance materials, etc.
- Depending on the overlap between electron and hole at the X point: trivial semimetal or topological insulator

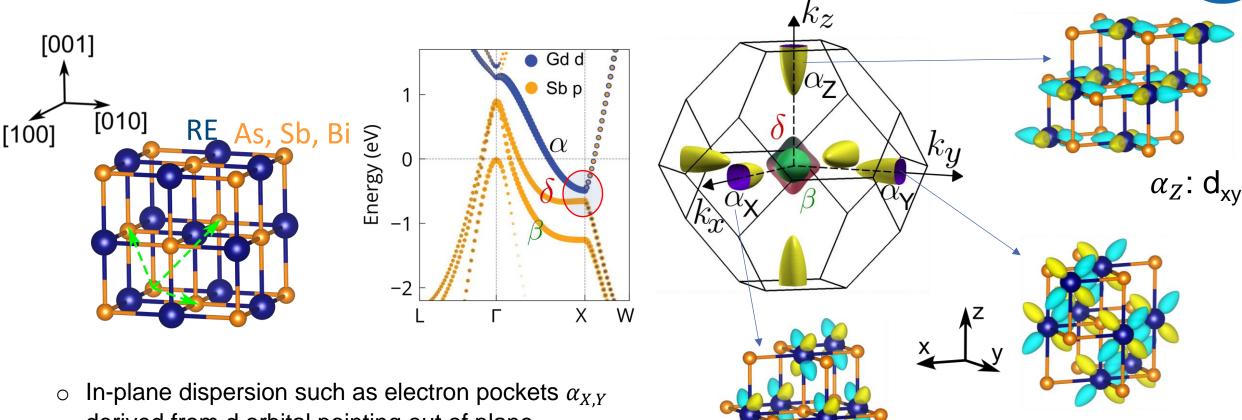
=> How to control topological property of a given RE-V?

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 k_y

ALS Ho et al., ACS Nano 2023, 17, 21, 20991–20998
Natali et al., Progress in Materials Science 2013, 58, 1316–1360

Directional characteristic of electron pockets



- derived from d orbital pointing out of plane \circ Out-of-plane dispersion: electron pockets α
- \circ Out-of-plane dispersion: electron pockets α_Z derived from d orbital lying in-plane

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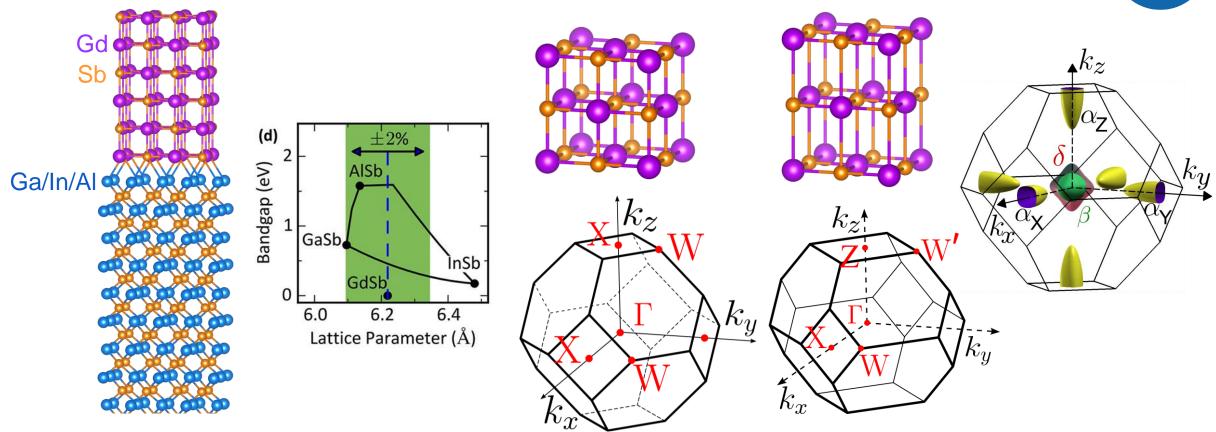
 α_X : d_v

Ho et al., ACS Nano 2023, 17, 21, 20991–20998

 $\alpha_Y: \mathsf{d}_{xz}$

Electronic topology under strain





- Electron pockets with orbitals lying perpendicular to film plane will not be affected by in-plane strain
- Electron pocket at Z with in-plane dxy orbital will be more affected

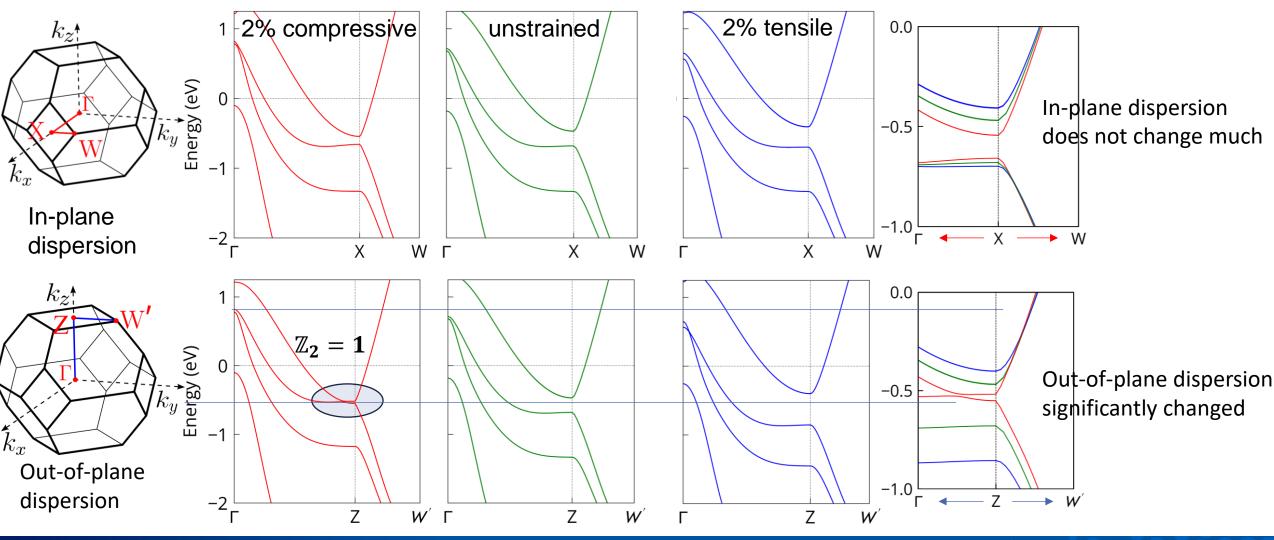
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Inbar, Ho et al., APL Mater. 2023, 11, 111106

Effect of strain to band dispersion and band topology



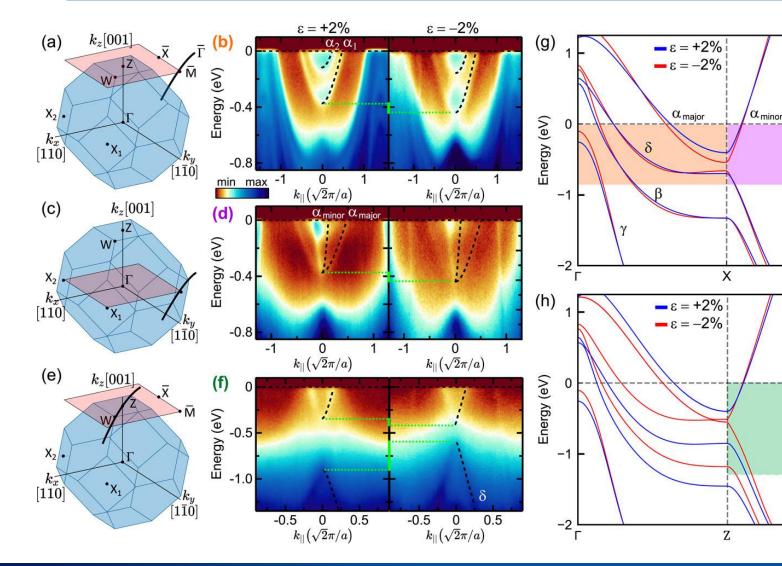


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Effect of strain to band dispersion and band topology





In-plane electron pockets: lower energy for compressive strain than that of tensile one In-plane hole pocket: relatively unchanged

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- Out-of-plane electron pockets: lower energy for compressive strain than that of tensile one
- Out-of-plane hole pocket: moving up quite significant, lowering the gap at Z

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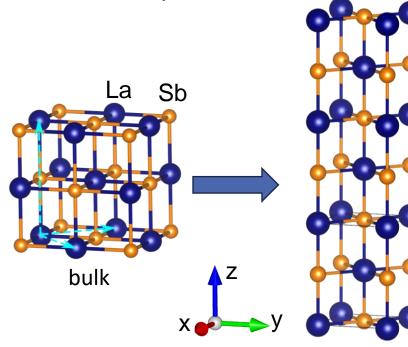
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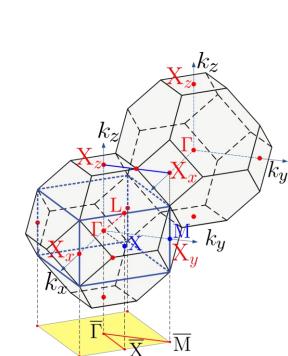
Electronic structure in ultra-thin film limit

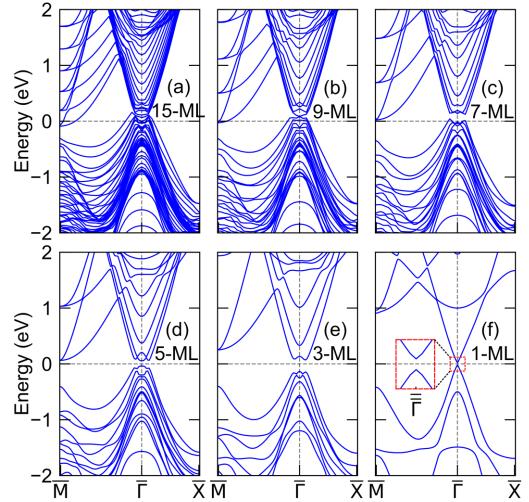




- Electron pocket along z are much less affected
- => band inversion at BZ center
- Starting from 7ML, a gap is opened throughout the whole BZ of 2D => quasi 2D TI



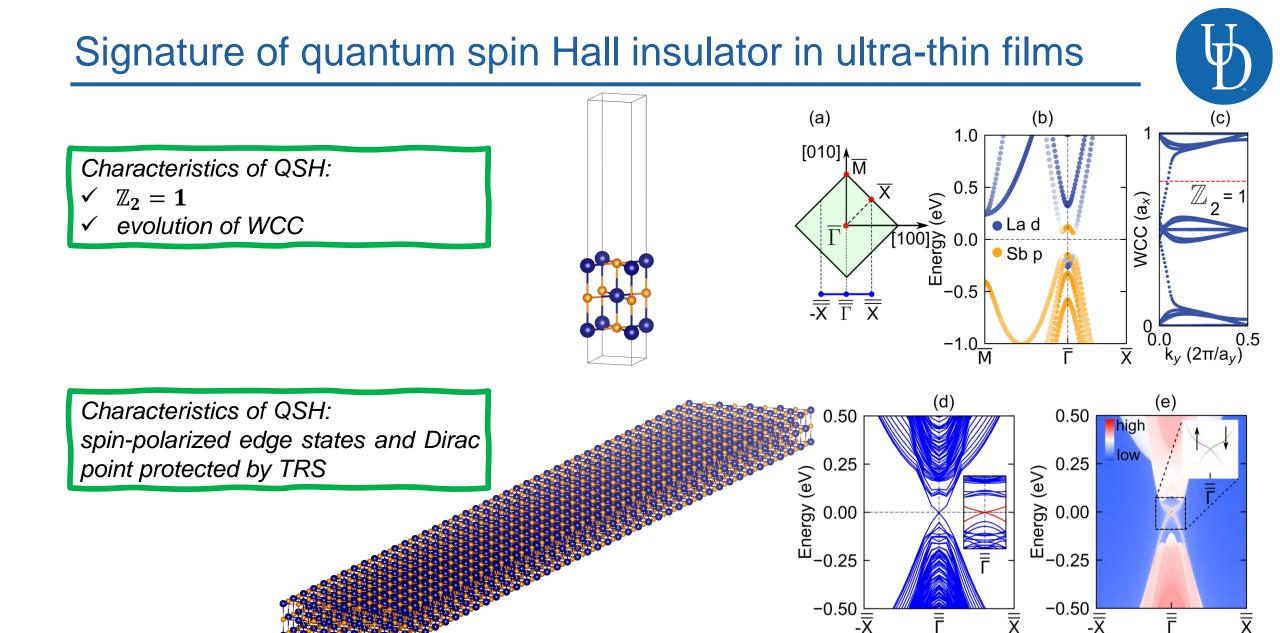




Quasi 2D film

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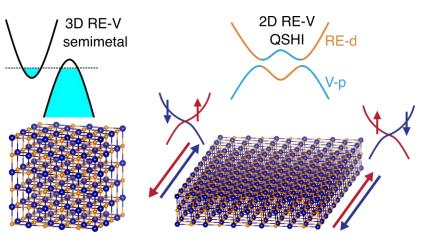
Ho et al., ACS Nano 2023, 17, 21, 20991–20998



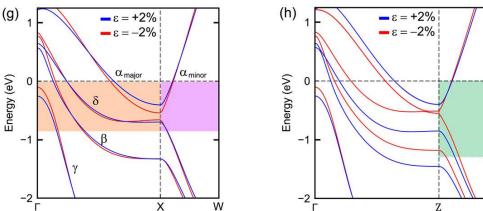
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Conclusion



- ✓ Observation of phase transition for LaSb from a trivial semimetal in the bulk to a sizeable gap QSH insulator in the ultrathin film limit characterized by $\mathbb{Z}_2 = 1$, TRS-protected Dirac point, and spin-polarized edge states
- The origin of the QSH phase is due to inverted band feature between La-d and Sb-p at Γ and gap opening by SOC.
- This phenomenon could be observed for other RE-Vs



- Observation of phase transition for GdSb from a trivial semimetal to topological insulator phase characterized by $\mathbb{Z}_2 = 1$ due to expitaxial strain
- Origin of the topological phase is due to band inversion at the Z point tunable by expitaxial strain.
- Epitaxial strain is an effective way to tune electronic structure of RE-Vs

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